

Kazuya Yamamura

List of Publications by Year in descending order

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141
papers

3,702
citations

147566

31
h-index

155451

55
g-index

143
all docs

143
docs citations

143
times ranked

1584
citing authors

#	ARTICLE	IF	CITATIONS
1	Breaking the 10 ^{−6} nm barrier in hard-X-ray focusing. <i>Nature Physics</i> , 2010, 6, 122-125.	6.5	484
2	Efficient focusing of hard x rays to 25nm by a total reflection mirror. <i>Applied Physics Letters</i> , 2007, 90, 051903.	1.5	203
3	Microstitching interferometry for x-ray reflective optics. <i>Review of Scientific Instruments</i> , 2003, 74, 2894-2898.	0.6	149
4	Plasma assisted polishing of single crystal SiC for obtaining atomically flat strain-free surface. <i>CIRP Annals - Manufacturing Technology</i> , 2011, 60, 571-574.	1.7	135
5	Relative angle determinable stitching interferometry for hard x-ray reflective optics. <i>Review of Scientific Instruments</i> , 2005, 76, 045102.	0.6	119
6	Development of plasma chemical vaporization machining. <i>Review of Scientific Instruments</i> , 2000, 71, 4627.	0.6	108
7	Fabrication of elliptical mirror at nanometer-level accuracy for hard x-ray focusing by numerically controlled plasma chemical vaporization machining. <i>Review of Scientific Instruments</i> , 2003, 74, 4549-4553.	0.6	99
8	Electro-chemical mechanical polishing of single-crystal SiC using CeO ₂ slurry. <i>Electrochemistry Communications</i> , 2015, 52, 5-8.	2.3	86
9	Development of scanning x-ray fluorescence microscope with spatial resolution of 30nm using Kirkpatrick-Baez mirror optics. <i>Review of Scientific Instruments</i> , 2006, 77, 103102.	0.6	85
10	Fabrication of elliptically figured mirror for focusing hard x rays to size less than 50nm. <i>Review of Scientific Instruments</i> , 2005, 76, 063708.	0.6	63
11	Nearly diffraction-limited line focusing of a hard-X-ray beam with an elliptically figured mirror. <i>Journal of Synchrotron Radiation</i> , 2002, 9, 313-316.	1.0	62
12	The study of fabrication of the x-ray mirror by numerically controlled plasma chemical vaporization machining: Development of the machine for the x-ray mirror fabrication. <i>Review of Scientific Instruments</i> , 2000, 71, 4620.	0.6	60
13	Two-dimensional Submicron Focusing of Hard X-rays by Two Elliptical Mirrors Fabricated by Plasma Chemical Vaporization Machining and Elastic Emission Machining. <i>Japanese Journal of Applied Physics</i> , 2003, 42, 7129-7134.	0.8	57
14	Atomic-scale flattening mechanism of 4H-SiC (0 0 0 1) in plasma assisted polishing. <i>CIRP Annals - Manufacturing Technology</i> , 2013, 62, 575-578.	1.7	57
15	Plasma CVM (chemical vaporization machining): an ultra precision machining technique using high-pressure reactive plasma. <i>Nanotechnology</i> , 1993, 4, 225-229.	1.3	56
16	Creation of perfect surfaces. <i>Journal of Crystal Growth</i> , 2005, 275, 39-50.	0.7	52
17	Computer numerically controlled plasma chemical vaporization machining with a pipe electrode for optical fabrication. <i>Applied Optics</i> , 1998, 37, 5198.	2.1	50
18	First-principles simulations of removal process in EEM (Elastic Emission Machining). <i>Computational Materials Science</i> , 1999, 14, 232-235.	1.4	48

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19	Damage-free improvement of thickness uniformity of quartz crystal wafer by plasma chemical vaporization machining. CIRP Annals - Manufacturing Technology, 2008, 57, 567-570.	1.7	48
20	Highly efficient planarization of sliced 4H-SiC (0001) wafer by slurryless electrochemical mechanical polishing. International Journal of Machine Tools and Manufacture, 2019, 144, 103431.	6.2	48
21	Plasma-assisted polishing of gallium nitride to obtain a pit-free and atomically flat surface. CIRP Annals - Manufacturing Technology, 2015, 64, 531-534.	1.7	47
22	Damage-free finishing of CVD-SiC by a combination of dry plasma etching and plasma-assisted polishing. International Journal of Machine Tools and Manufacture, 2017, 115, 38-46.	6.2	45
23	Adhesive-free adhesion between heat-assisted plasma-treated fluoropolymers (PTFE, PFA) and plasma-jet-treated polydimethylsiloxane (PDMS) and its application. Scientific Reports, 2018, 8, 18058.	1.6	45
24	Damage-free highly efficient polishing of single-crystal diamond wafer by plasma-assisted polishing. CIRP Annals - Manufacturing Technology, 2018, 67, 353-356.	1.7	43
25	Optimization of the plasma oxidation and abrasive polishing processes in plasma-assisted polishing for highly effective planarization of 4H-SiC. CIRP Annals - Manufacturing Technology, 2014, 63, 529-532.	1.7	42
26	Thinning of silicon-on-insulator wafers by numerically controlled plasma chemical vaporization machining. Review of Scientific Instruments, 2004, 75, 942-946.	0.6	40
27	Fabrication of Ultra Precision Optics by Numerically Controlled Local Wet Etching. CIRP Annals - Manufacturing Technology, 2007, 56, 541-544.	1.7	40
28	Competition between surface modification and abrasive polishing: a method of controlling the surface atomic structure of 4H-SiC (0001). Scientific Reports, 2015, 5, 8947.	1.6	40
29	Development of plasma chemical vaporization machining and elastic emission machining systems for coherent x-ray optics. , 2001, 4501, 30.		39
30	Investigation of anodic oxidation mechanism of 4H-SiC (0001) for electrochemical mechanical polishing. Electrochimica Acta, 2018, 271, 666-676.	2.6	39
31	Drastic Improvement in Adhesion Property of Polytetrafluoroethylene (PTFE) via Heat-Assisted Plasma Treatment Using a Heater. Scientific Reports, 2017, 7, 9476.	1.6	35
32	Diffraction-limited two-dimensional hard-x-ray focusing at the 100nm level using a Kirkpatrick-Baez mirror arrangement. Review of Scientific Instruments, 2005, 76, 083114.	0.6	33
33	Characterization of 4H-SiC (0001) surface processed by plasma-assisted polishing. International Journal of Advanced Manufacturing Technology, 2014, 72, 1-7.	1.5	33
34	Fabrication of optics by use of plasma chemical vaporization machining with a pipe electrode. Applied Optics, 2002, 41, 3971.	2.1	32
35	Development of mirror manipulator for hard-x-ray nanofocusing at sub-50-nm level. Review of Scientific Instruments, 2006, 77, 093107.	0.6	32
36	Polishing and planarization of single crystal diamonds: state-of-the-art and perspectives. International Journal of Extreme Manufacturing, 2021, 3, 022003.	6.3	31

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37	Figuring of plano-elliptical neutron focusing mirror by local wet etching. <i>Optics Express</i> , 2009, 17, 6414.	1.7	30
38	Observation of the Spatial Distribution of Gravitationally Bound Quantum States of Ultracold Neutrons and Its Derivation Using the Wigner Function. <i>Physical Review Letters</i> , 2014, 112, 071101.	2.9	30
39	Atomic-scale finishing of carbon face of single crystal SiC by combination of thermal oxidation pretreatment and slurry polishing. <i>Applied Surface Science</i> , 2018, 434, 40-48.	3.1	29
40	Atomic-scale and damage-free polishing of single crystal diamond enhanced by atmospheric pressure inductively coupled plasma. <i>Carbon</i> , 2021, 182, 175-184.	5.4	28
41	High-Integrity Finishing of 4H-SiC (0001) by Plasma-Assisted Polishing. <i>Advanced Materials Research</i> , 2010, 126-128, 423-428.	0.3	27
42	Obtaining Atomically Smooth 4H-SiC (0001) Surface by Controlling Balance Between Anodizing and Polishing in Electrochemical Mechanical Polishing. <i>Nanomanufacturing and Metrology</i> , 2019, 2, 140-147.	1.5	27
43	Deterministic retrieval of surface waviness by means of topography with coherent X-rays. <i>Journal of Synchrotron Radiation</i> , 2002, 9, 223-228.	1.0	26
44	Polishing Characteristics of Silicon Carbide by Plasma Chemical Vaporization Machining. <i>Japanese Journal of Applied Physics</i> , 2006, 45, 8277-8280.	0.8	26
45	Ultrasonic-assisted anodic oxidation of 4H-SiC (0001) surface. <i>Electrochemistry Communications</i> , 2019, 100, 1-5.	2.3	26
46	Laser beam intensity profile transformation with a fabricated mirror. <i>Applied Optics</i> , 1997, 36, 551.	2.1	24
47	Development of numerically controlled local wet etching. <i>Science and Technology of Advanced Materials</i> , 2007, 8, 158-161.	2.8	24
48	Improving the grindability of titanium alloy Ti-6Al-4V with the assistance of ultrasonic vibration and plasma electrolytic oxidation. <i>CIRP Annals - Manufacturing Technology</i> , 2017, 66, 345-348.	1.7	24
49	Etching characteristics of local wet etching of silicon in HF/HNO ₃ mixtures. <i>Surface and Interface Analysis</i> , 2008, 40, 1011-1013.	0.8	21
50	Comparison between adhesion properties of adhesive bonding and adhesive-free adhesion for heat-assisted plasma-treated polytetrafluoroethylene (PTFE). <i>Journal of Adhesion</i> , 2020, 96, 776-796.	1.8	21
51	Damage-free highly efficient plasma-assisted polishing of a 20-mm square large mosaic single crystal diamond substrate. <i>Scientific Reports</i> , 2020, 10, 19432.	1.6	21
52	Efficient and slurryless ultrasonic vibration assisted electrochemical mechanical polishing for 4H-SiC wafers. <i>Ceramics International</i> , 2022, 48, 7570-7583.	2.3	21
53	Ultraprecision Machining Utilizing Numerically Controlled Scanning of Localized Atmospheric Pressure Plasma. <i>Japanese Journal of Applied Physics</i> , 2006, 45, 8270-8276.	0.8	20
54	Ultrasoother reaction-sintered silicon carbide surface resulting from combination of thermal oxidation and ceria slurry polishing. <i>Optics Express</i> , 2013, 21, 14780.	1.7	19

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55	Effects of polishing pressure and sliding speed on the material removal mechanism of single crystal diamond in plasma-assisted polishing. <i>Diamond and Related Materials</i> , 2022, 124, 108899.	1.8	19
56	Novel SiC wafer manufacturing process employing three-step slurryless electrochemical mechanical polishing. <i>Journal of Manufacturing Processes</i> , 2021, 70, 350-360.	2.8	18
57	Wave-optical analysis of submicron focus of hard x-ray beams by reflective optics. , 2002, 4782, 271.		17
58	Temperature Dependence of Plasma Chemical Vaporization Machining of Silicon and Silicon Carbide. <i>Materials Science Forum</i> , 0, 600-603, 847-850.	0.3	17
59	Atomic-scale planarization of 4H-SiC (0001) by combination of thermal oxidation and abrasive polishing. <i>Applied Physics Letters</i> , 2013, 103, 111603.	1.5	17
60	Comparison of thermal oxidation and plasma oxidation of 4H-SiC (0001) for surface flattening. <i>Applied Physics Letters</i> , 2014, 104, .	1.5	17
61	Dominant factors and their action mechanisms on material removal rate in electrochemical mechanical polishing of 4H-SiC (0001) surface. <i>Applied Surface Science</i> , 2021, 562, 150130.	3.1	17
62	Improvement of the thickness distribution of a quartz crystal wafer by numerically controlled plasma chemical vaporization machining. <i>Review of Scientific Instruments</i> , 2005, 76, 096103.	0.6	16
63	Surface Modification and Microstructuring of 4H-SiC(0001) by Anodic Oxidation with Sodium Chloride Aqueous Solution. <i>ACS Applied Materials & Interfaces</i> , 2019, 11, 2535-2542.	4.0	16
64	Development of fabrication process for aspherical neutron focusing mirror using numerically controlled local wet etching with low-pressure polishing. <i>Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment</i> , 2011, 634, S112-S116.	0.7	15
65	Preliminary Study on Chemical Figuring and Finishing of Sintered SiC Substrate Using Atmospheric Pressure Plasma. <i>Procedia CIRP</i> , 2012, 3, 335-339.	1.0	15
66	Mechanism analysis on finishing of reaction-sintered silicon carbide by combination of water vapor plasma oxidation and ceria slurry polishing. <i>Optical Engineering</i> , 2015, 54, 055106.	0.5	14
67	Comparative analysis on surface property in anodic oxidation polishing of reaction-sintered silicon carbide and single-crystal 4H silicon carbide. <i>Applied Physics A: Materials Science and Processing</i> , 2016, 122, 1.	1.1	14
68	Effect of rubber compounding agent on adhesion strength between rubber and heat-assisted plasma-treated polytetrafluoroethylene (PTFE). <i>Journal of Adhesion</i> , 2019, 95, 242-257.	1.8	14
69	Preliminary Study on Highly Efficient Polishing of 4H-SiC by Utilization of Anodic Oxidation. <i>Advanced Materials Research</i> , 0, 1017, 509-514.	0.3	13
70	Atomic-scale and pit-free flattening of GaN by combination of plasma pretreatment and time-controlled chemical mechanical polishing. <i>Applied Physics Letters</i> , 2015, 107, .	1.5	13
71	Etching Characteristics of Quartz Crystal Wafers Using Argon-Based Atmospheric Pressure CF ₄ Plasma Stabilized by Ethanol Addition. <i>Nanomanufacturing and Metrology</i> , 2019, 2, 168-176.	1.5	13
72	Catalytic Properties of Chemically Modified Graphene Sheets to Enhance Etching of Ge Surface in Water. <i>Journal of Physical Chemistry C</i> , 2020, 124, 6121-6129.	1.5	12

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73	High-quality plasma-assisted polishing of aluminum nitride ceramic. CIRP Annals - Manufacturing Technology, 2020, 69, 301-304.	1.7	12
74	Polishing of Tungsten Carbide by Combination of Anodizing and Silica Slurry Polishing. Journal of the Electrochemical Society, 2017, 164, E352-E359.	1.3	11
75	Optimization of Gas Composition Used in Plasma Chemical Vaporization Machining for Figuring of Reaction-Sintered Silicon Carbide with Low Surface Roughness. Scientific Reports, 2018, 8, 2376.	1.6	11
76	AFM Observation of Initial Oxidation Stage of 4H-SiC (0001) in Electrochemical Mechanical Polishing. Procedia CIRP, 2018, 68, 735-740.	1.0	11
77	Novel highly-efficient and dress-free polishing technique with plasma-assisted surface modification and dressing. Precision Engineering, 2021, 72, 224-236.	1.8	11
78	Comparison of surface and subsurface damage of mosaic single-crystal diamond substrate processed by mechanical and plasma-assisted polishing. Diamond and Related Materials, 2021, 119, 108555.	1.8	11
79	Plasma Chemical Vaporization Machining (CVM) for Fabrication of Optics. Japanese Journal of Applied Physics, 1998, 37, L894-L896.	0.8	10
80	Submicron focusing of hard x-ray beam by elliptically figured mirrors for scanning x-ray microscopy. , 2002, , .		10
81	High-reflectivity (m=4) elliptical neutron focusing supermirror fabricated by numerically controlled local wet etching with ion beam sputter deposition. Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment, 2010, 616, 193-196.	0.7	10
82	Improvement in Adhesion between Polytetrafluoroethylene (PTFE) and Electroless-Plated Copper Film Using Heat-Assisted Plasma Treatment. Hyomen Gijutsu/Journal of the Surface Finishing Society of Japan, 2016, 67, 551-556.	0.1	10
83	Cross-sectional observation of a weak boundary layer in polytetrafluoroethylene (PTFE) using scanning electron microscope. Polymer Journal, 2022, 54, 79-81.	1.3	10
84	Effects of He and Ar Heat-Assisted Plasma Treatments on the Adhesion Properties of Polytetrafluoroethylene (PTFE). Polymers, 2021, 13, 4266.	2.0	10
85	Aspheric Surface Fabrication in nm-level Accuracy by Numerically Controlled Plasma Chemical Vaporization Machining (CVM) and Elastic Emission Machining (EEM). , 2002, 4782, 265.		9
86	Fabrication technology of hard x-ray aspherical mirror optics and application to nanospectroscopy. , 2004, , .		9
87	Damage-Free Dry Polishing of 4H-SiC Combined with Atmospheric-Pressure Water Vapor Plasma Oxidation. Japanese Journal of Applied Physics, 2011, 50, 08JG05.	0.8	9
88	Etching characteristics of GaN by plasma chemical vaporization machining. Surface and Interface Analysis, 2008, 40, 1566-1570.	0.8	8
89	One-dimensional neutron focusing with large beam divergence by 400mm-long elliptical supermirror. Journal of Physics: Conference Series, 2012, 340, 012034.	0.3	8
90	Influence of air contamination during heat-assisted plasma treatment on adhesion properties of polytetrafluoroethylene (PTFE). RSC Advances, 2019, 9, 22900-22906.	1.7	8

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91	Adhesive-Free Adhesion between Plasma-Treated Glass-Cloth-Containing Polytetrafluoroethylene (GCâ€“PTFE) and Stainless Steel: Comparison between GCâ€“PTFE and Pure PTFE. <i>Polymers</i> , 2022, 14, 394.	2.0	8
92	Effect of Si interlayers on the magnetic and mechanical properties of Fe/Ge neutron polarizing multilayer mirrors. <i>Journal of Applied Physics</i> , 2012, 111, 063904.	1.1	7
93	Efficient processing of reaction-sintered silicon carbide by anodically oxidation-assisted polishing. <i>Optical Engineering</i> , 2015, 54, 105113.	0.5	7
94	Preliminary study on atmospheric-pressure plasma-based chemical dry figuring and finishing of reaction-sintered silicon carbide. <i>Optical Engineering</i> , 2016, 55, 105102.	0.5	7
95	Radiolytic Synthesis of Pt-Particle/ABS Catalysts for H ₂ O ₂ Decomposition in Contact Lens Cleaning. <i>Nanomaterials</i> , 2017, 7, 235.	1.9	7
96	High-precision figured thin supermirror substrates for multiple neutron focusing device. <i>Journal of Physics: Conference Series</i> , 2012, 340, 012016.	0.3	6
97	Investigation of Removal Mechanism of Sapphire in Plasma Assisted Polishing. <i>Key Engineering Materials</i> , 2014, 625, 458-462.	0.4	6
98	Surface gradient integrated profiler for X-ray and EUV optics. <i>Science and Technology of Advanced Materials</i> , 2007, 8, 177-180.	2.8	5
99	Atomic-scale insights into the origin of rectangular lattice in nanographene probed by scanning tunneling microscopy. <i>Physical Review B</i> , 2021, 103, .	1.1	5
100	Strong Biomimetic Immobilization of Pt-Particle Catalyst on ABS Substrate Using Polydopamine and Its Application for Contact-Lens Cleaning with H ₂ O ₂ . <i>Nanomaterials</i> , 2020, 10, 114.	1.9	5
101	Development of a figure correction method having spatial resolution close to 0.1 mm. , 2004, 5193, 105.		4
102	Fabrication of damage-free Johansson-type doubly curved crystal spectrometer substrate by numerically controlled local wet etching. <i>Nuclear Instruments and Methods in Physics Research, Section A: Accelerators, Spectrometers, Detectors and Associated Equipment</i> , 2010, 616, 281-284.	0.7	4
103	Atmospheric pressure plasma liquid deposition of copper nanoparticles onto poly(4-vinylpyrdine)-grafted-poly(tetrafluoroethylene) surface. <i>Transactions of the Materials Research Society of Japan</i> , 2010, 35, 817-820.	0.2	4
104	The Improvement of Removal Function in Local Wet Etching by Using Eccentric Rotation System. <i>Key Engineering Materials</i> , 2012, 516, 504-509.	0.4	4
105	Study on Removal Mechanism of Sapphire in Plasma Assisted Polishing. <i>Advanced Materials Research</i> , 0, 1136, 317-320.	0.3	4
106	A Simulation Study on Figure Error Correction Using Near-Gaussian Removal Function in Numerical Controlled Local Wet Etching. <i>Key Engineering Materials</i> , 2012, 523-524, 276-280.	0.4	3
107	Improvement of the Thickness Distribution of AT Cut Quartz Crystal Wafer by Open-air Type Plasma Chemical Vaporization Machining. <i>E-Journal of Surface Science and Nanotechnology</i> , 2007, 5, 41-44.	0.1	3
108	Charge Utilization Efficiency and Side Reactions in the Electrochemical Mechanical Polishing of 4H-SiC (0001). <i>Journal of the Electrochemical Society</i> , 2022, 169, 023501.	1.3	3

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109	Nanocarbon-Induced Etching Property of Semiconductor Surfaces: Testing Nanocarbon's Catalytic Activity for Oxygen Reduction Reaction at a Single-Sheet Level. ECS Journal of Solid State Science and Technology, 2022, 11, 041001.	0.9	3
110	Figuring of elliptical hard X-ray focusing mirror using 1-dimensional numerically controlled local wet etching. Surface and Interface Analysis, 2008, 40, 1014-1018.	0.8	2
111	Improvement of thickness uniformity of bulk silicon wafer by numerically controlled local wet etching. Journal of Crystal Growth, 2009, 311, 2560-2563.	0.7	2
112	Fabrication of plano-elliptical neutron focusing supermirror by numerically controlled local wet etching with ion beam sputter deposition. Journal of Physics: Conference Series, 2010, 251, 012077.	0.3	2
113	Neutron beam focusing using large-m supermirrors coated on precisely-figured aspheric surfaces. Journal of Physics: Conference Series, 2010, 251, 012076.	0.3	2
114	Figuring of Aspherical Metal Mirror Substrate for Neutron Focusing by Numerically Controlled Electrochemical Machining. Key Engineering Materials, 2012, 523-524, 29-33.	0.4	2
115	Evaluation of Surface Roughness and Subsurface Damage of 4H-SiC Processed by Different Finishing Techniques. Key Engineering Materials, 0, 523-524, 19-23.	0.4	2
116	Surface Modification of Fluoropolymer Using Open-Air Plasma Treatment at Atmospheric Pressure with Ar, Ar ^{1/4} O ₂ , and Ar ^{1/4} H ₂ for Application in High Adhesion Metal Wiring Patterns. Hyomen Gijutsu/Journal of the Surface Finishing Society of Japan, 2018, 69, 155-162.	0.1	2
117	Improvements in graphene growth on 4H-SiC(0001) using plasma induced surface oxidation. Journal of Applied Physics, 2019, 126, 065301.	1.1	2
118	Improved Catalytic Durability of Pt-Particle/ABS for H ₂ O ₂ Decomposition in Contact Lens Cleaning. Nanomaterials, 2019, 9, 342.	1.9	2
119	Plasma-CVM (Chemical Vaporization Machining). , 0, , 587-606.		1
120	Uniformalization of AT cut quartz crystal wafer thickness using open-air type plasma CVM process. Surface and Interface Analysis, 2008, 40, 1007-1010.	0.8	1
121	Quadruple Stacked Elliptical Supermirror Device for One Dimensional Neutron Focusing. Key Engineering Materials, 2012, 523-524, 272-275.	0.4	1
122	Noncontact Figuring of Millimeter-Thick Elliptical Mirror Substrate by Numerically Controlled Local Wet Etching. Key Engineering Materials, 2012, 516, 361-366.	0.4	1
123	Investigation on the formation of projections and cracks in anodic oxidation of reaction-sintered silicon carbide. IOP Conference Series: Materials Science and Engineering, 2017, 167, 012064.	0.3	1
124	Ultraprecision Finishing Process for Improving Thickness Distribution of Quartz Crystal Wafer by Utilizing Atmospheric Pressure Plasma. , 2006, , .		0
125	Surface Gradient Integrated Profiler for X-ray and EUV Optics's Calibration of the rotational angle error of the rotary encoders. AIP Conference Proceedings, 2007, , .	0.3	0
126	Fabrication of X-ray Mirror for Hard X-ray Diffraction Limited Nanofocusing. AIP Conference Proceedings, 2007, , .	0.3	0

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127	Ultraprecision Machining Method for Ultraprecise Aspherical Mirror. The Review of Laser Engineering, 2007, 35, 162-167.	0.0	0
128	Figuring of Elliptical Neutron Focusing Mirror Using Numerically Controlled Local Wet Etching. Key Engineering Materials, 0, 407-408, 376-379.	0.4	0
129	Improvement of Thickness Uniformity of Bulk Silicon Wafer by Numerically Controlled Local Wet Etching. Key Engineering Materials, 0, 407-408, 372-375.	0.4	0
130	Fabrication of Ultraprecision Millimeter-Thick Elliptical Neutron Focusing Mirror Substrate by Local Wet Etching. Key Engineering Materials, 0, 447-448, 208-212.	0.4	0
131	Improvement in Thickness Uniformity of Thick SOI by Numerically Controlled Local Wet Etching. Journal of Nanoscience and Nanotechnology, 2011, 11, 2910-2915.	0.9	0
132	Finishing of AT-Cut Quartz Crystal Wafer with Nanometric Thickness Uniformity by Pulse-Modulated Atmospheric Pressure Plasma Etching. Journal of Nanoscience and Nanotechnology, 2011, 11, 2922-2927.	0.9	0
133	Evaluation of Surface Roughness of Quartz Glass Substrate in Fabrication Process for Neutron Focusing Mirror. Advanced Materials Research, 2011, 325, 647-652.	0.3	0
134	Study on <i>In Situ</i> Etching Rate Monitoring in Numerically Controlled Local Wet Etching. Key Engineering Materials, 0, 523-524, 34-39.	0.4	0
135	Neutron Focusing by a Kirkpatrick-Baez Type Super-Mirror. , 2015, , .		0
136	Development of Damage-free Figuring and Finishing Techniques for Ceramics Materials by Utilizing Reactive Plasma. Funtai Oyobi Fumatsu Yakin/Journal of the Japan Society of Powder and Powder Metallurgy, 2018, 65, 654-658.	0.1	0
137	Selective Etching of Semiconductor Surfaces by Catalytic Activity of Nanocarbon. Vacuum and Surface Science, 2021, 64, 352-357.	0.0	0
138	Figuring of Neutron Focusing Elliptical Mirror Substrate by Numerically Controlled Local Wet Etching. Journal of the Japan Society for Precision Engineering, 2013, 79, 813-817.	0.0	0
139	Development of High-Efficiency Damage-Free Polishing Technology for Large-Sized Single Crystal Diamond Substrates by Plasma-Assisted Polishing. Journal of the Japan Society for Precision Engineering, 2022, 88, 133-136.	0.0	0
140	Separation of Neighboring Terraces on a Flattened Si(111) Surface by Selective Etching along Step Edges Using Total Wet Chemical Processing. Langmuir, 2022, 38, 3748-3754.	1.6	0
141	Slurryless Plasma-Assisted Polishing and Electrochemical Mechanical Polishing of Difficult to Polish Materials. Journal of the Japan Society for Precision Engineering, 2022, 88, 440-444.	0.0	0